



Docket Number: P-0381.020-US
Client Reference: P-0381.020-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

LOF et al.

Group Art Unit: 1756

Application No.: 10/705,783

Examiner:

Filed: November 12, 2003

Confirmation No.: 5222

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
D.R.	DIERICHS (081468-0308270)	10/775,326	02/11/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
↓	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
↓	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
D.R.	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty.
Dkt. No.

M#

Client Ref.

306524

P-0381.020-US

Applicant: LOF et al.

Appln. No.: 10/705,783

Filing Date: November 12, 2003

Examiner:

Group Art Unit: 1756

2851

Date: June 22, 2004

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
DR	AR	2004/0075895 A1	04/2004	LIN		
DR	BR	2004/0109237 A1	06/2004	EPPL et al.		
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					
	IR					
	JR					
	KR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
DR	LR	WO 03/077037	09/2003	PCT	ROSTALSKI			
DR	MR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.		X	
DR	NR	DD 221 563	04/1985	GERMANY	PFORR et al.		X	
	OR							
	PR							
	QR							
	RR							
	SR							
	TR							

OTHER (Including in this order: Author, Title, Periodical Name, Date, Reprint, Pages, etc.)

DR	UR	B. LIN, "The k_3 coefficient in nonparaxial A/NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
	VR				
	WR				
	XR				
	YR				
	ZR				
	AAR				
	BBR				
	CCR				

Examiner

Date Considered: 5/6/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office

Atty.
Dkt. No.

M#

Client Ref.

306524

P-0381.020-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Joeri LOF *et al.*

Appln. No.: ~~TO BE ASSIGNED~~ 10/705783

Filing Date: November 12, 2003

Date: November 12, 2003

Page

1

of

3

Examiner: Unknown

Group Art Unit: Unknown

2851

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
D.R.	AR	3,573,975	04/1971	Dhaka <i>et al.</i>	117	212	
	BR	3,648,587	03/1972	Stevens	95	44	
	CR	4,346,164	08/1982	Tabarelli <i>et al.</i>	430	311	
	DR	4,396,705	08/1983	Akeyama <i>et al.</i>	430	326	
	ER	4,480,910	11/1984	Takanashi <i>et al.</i>	355	30	
	FR	4,509,852	04/1985	Tabarelli <i>et al.</i>	355	30	
	GR	5,040,020	08/1991	Rauschenbach <i>et al.</i>	355	53	
	HR	5,121,256	06/1992	Corle <i>et al.</i>	359	664	
	IR	5,610,683	03/1997	Takahashi	355	53	
	JR	5,715,039	02/1998	Fukuda <i>et al.</i>	355	53	
	KR	5,825,043	10/1998	Suwa	250	548	
	LR	5,900,354	05/1999	Batchelder	430	395	
	MR	6,191,429	02/2001	Suwa	250	548	
D.R.	NR	6,560,032	05/2003	Hatano	359	656	

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclose	No
D.R.	OR	WO 99/49504	09/1999	PCT	Fukami <i>et al.</i>	X		X	
	PR	EP 0023231	02/1981	Europe	Tabarelli <i>et al.</i>	X			
	QR	EP 0418427	03/1991	Europe	Miyake	X		X	
	RR	EP 1039511	09/2000	Europe	Murakimi <i>et al.</i>	X		X	
	SR	DD 224448	07/1985	German	Hesse <i>et al.</i>		X		
	TR	DD 242880	02/1987	German	Kuch		X		
	UR	FR 2474708	07/1981	France	Letellier		X		
	VR	JP 62-065326	03/1987	Japan	Moriuchi	X			
	WR	JP 62-121417	06/1987	Japan	Nakazawa	X			
D.R.	XR	JP 63-157419	06/1988	Japan	Nakasuji	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

	YR	EP Search Report for EP 02257938 dated September 25, 2003							
D.R.	ZR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001							
D.R.	AAR	M. Switkes <i>et al.</i> , "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356							
D.R.	BBR	M. Switkes <i>et al.</i> , "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002							

Examiner

[Signature]

Date Considered:

5/16/2005

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FORM PTO-1449 (modified)
To: U.S. Department of Commerce
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Patent and Trademark Office

Atty. No.	M#	Client Ref.
Dkt. No.	306781	P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant:	Joeri LOF <i>et al.</i>
Appl. No.:	TO BE ASSIGNED 10/725783
Filing Date:	November 12, 2003
Examiner:	Unknown
Group Art Unit:	Unknown

Date: November 12, 2003 Page 2 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
D.R.	CCR 6,603,130	08/2003	Bisschops <i>et al.</i>	250	492.1	
	DDR 6,633,365	10/2003	Suenaga	355	53	
	EER 2002/0163629	11/2002	Switkes <i>et al.</i>	355	53	
	FFR 2003/0123040	07/2003	Almogoy	355	69	
D.R.	GGR 2003/0174408	09/2003	Rostalski <i>et al.</i>	359	642	
	HHR					
	IIR					
	JJR					
	KKR					
	LLR					
	MMR					
	NNR					
	OOR					
	PPR					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclose	No
D.R.	QQR JP 04-305915	10/1992	Japan	Ozeki <i>et al.</i>	X			
	RRR JP 04-305917	10/1992	Japan	Ozeki <i>et al.</i>	X			
	SSR JP 06-124873	05/1994	Japan	Takahashi	X		X	
	TTR JP 07-220990	08/1995	Japan	Fukuda <i>et al.</i>	X			
	UUR JP 10-228661	08/1998	Japan	Kurokawa	X			
	VVR JP 10-255319	09/1998	Japan	Suenaga <i>et al.</i>	X			
	WWR JP 10-303114	11/1998	Japan	Suwa	X		X	
	XXR JP 10-340846	12/1998	Japan	Kudo	X		X	
D.R.	YYR JP 2001-091849	04/2001	Japan	Aizaki <i>et al.</i>	X			
	ZZR							

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

D.R.	AAAR	B.J. Lin, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
D.R.	BBBR	B.J. Lin, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			

Examiner 102 nll eds Date Considered: 5/6/03

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FORM PTO-1449 (modified)
To: U.S. Department of Commerce
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Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
	306781	P-0381.010-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Joeri LOF *et al.*

Appln. No.: ~~TO BE ASSIGNED~~ 10/705783

Filing Date: November 12, 2003

Examiner: Unknown Group Art Unit: Unknown

Date: November 12, 2003 Page 3 of 3

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	CCC					
	DDD					
	EEE					

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
	FFFF				Enclosed	No
	GGG					

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

D.R.	HHH	B.J. Lin, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269				
	IIIR	G.W.W. Stevens, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72				
	JJJR	S. Owa et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003				
	KKK	S. Owa et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)				
	LLL	Nikon Precision Europe GmbH, "Investor Relations - Nikon's Real Solutions", May 15, 2003				
	MMM	H. Kawata et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36				
	NNN	J.A. Hoffnagle et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309				
	OOO	B.W. Smith et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003				
	PPP	H. Kawata et al., "Fabrication of 0.2µm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177				
D.R.	QQQ	G. Owen et al., "1/8µm Optical Lithography", J. Vac. Sci. Technol. B., Vol. 10, No. 6, November/December 1992, pp. 3032-3036				
	RRR					
	SSS					
	TTT					
	UUU					
	VVV					
	WWW					
	XXX					
	YYY					

Examiner *Bentley*

Date Considered: 5/6/2005

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FORM PTO-1449 (modified)
To: U.S. Department of Commerce
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Patent and Trademark Office

Atty. Dkt. No.	M#	Client Ref.
081468	0306524	P-0381.020-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Joeri LOF et al.	
Appln. No.: 10/705,783	
Filing Date: November 12, 2003	
Examiner: Unassigned	Group Art Unit: Unassigned

Date: March 31, 2004 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR					
	BR					
	CR					
	DR					
	ER					
	FR					
	GR					
	HR					

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Endose	No
D.R.	IR	JP 07-132262	05/1995	Japan	Hirakawa et al.	X			
	JR	JP 58-202448	11/1983	Japan	Kawamura et al.	X			
	KR	WO 2004/019128	03/2004	PCT	Omura et al.				
D.R.	LR	WO 03/077036	092003	PCT	Schuster	X			
	MR								
	NR								
	OR								
	PR								
	QR								
	RR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

D.R.	SR	Copy of European Search Report for EP Application No. 02257822.3 dated January 20, 2004							
	TR	S. Owa et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51							
	UR	H. Hata, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22							
	VR	T. Matsuyama et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004							
	WR	"Depth-of-Focus Enhancement Using High Refractive Index Layer on the Imaging Layer", IBM Technical Disclosure Bulletin, Vol. 27, No. 11, April 1985, p. 6521							
D.R.	XR	A. Suzuki, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004							
	YR								

Examiner *[Signature]* Date Considered: 5/6/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

Docket Number: 081468-0306524
Client Reference: P-0381.020-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



Re the Application of
JOERI LOF et al.
Application No.: 10/705,783

Group Art Unit:

Examiner: Unassigned

Filed: November 12, 2003

Confirmation No.: Unassigned

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

INFORMATION DISCLOSURE STATEMENT

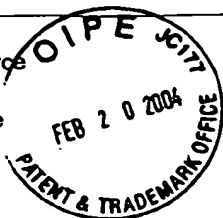
Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
D.R.	Joeri LOF et al.	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Helmar VAN SANTEN et al.	10/743,271	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Johannes C.H. MULKENS et al.	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Klaus SIMON et al.	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Joannes T. DESMIT et al.	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Antonius T.A.M. DERKSEN et al.	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Arno J. BLEEKER	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	Bob STREEFKERK et al.	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
D.R.	Joeri LOF et al.	10/705,816	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

The Examiner's initials indicates he/she has considered the cited application relative to the subject application.



Atty. Dkt. No.	M#	Client Ref.
081468	0306524	P-0381.020-US

**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Applicant: Joeri LOF et al.	
Appln. No.: 10/705,783	
Filing Date: November 12, 2003	
Examiner: Unassigned	Group Art Unit: Unassigned

Date: February 20, 2004 Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
<i>D.R.</i>	AR	2004/0000627A1	01/01/2004	Karl-Heinz SCHUSTER	-	-	
<i>D.R.</i>	BR	6,600,547	07/29/2003	WATSON et al.	-	-	
<i>D.R.</i>	CR	2004/0021844 A1	02/05/2004	Yutaka SUENAGA	-	-	
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						

FOREIGN PATENT DOCUMENTS

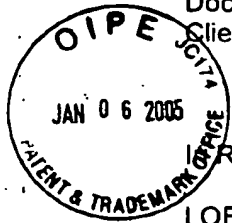
		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract	Translation Readily Available
						Enclosed	No
	NR						
	OR						
	PR						
	QR						
	RR						
	SR						
	TR						
	UR						
	VR						
	WR						

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

<i>D.R.</i>	XR	H. Hogan, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3			
<i>D.R.</i>	YR	S. Owa and N. Nagasaka, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.			
	ZR				
	AAR				
	BBR				
	CCR				

Examiner *Butter* Date Considered: *5/6/2005*

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.



Docket Number: 081468-0306524
Client Reference: P-0381.020-US

JPW
PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Re the Application of

LOF et al.

Group Art Unit: 1756

Application No.: 10/705,783

Examiner: Unassigned

Filed: November 12, 2003

Confirmation No.: 5222

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

January 6, 2005

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
<i>D.R.</i>	STREEFKERK et al. (081468-0309421)	10/844,575	05/13/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

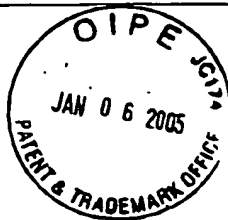
It is respectfully requested that this application and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent application is not to be construed as a waiver of secrecy as to that application now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) **PLEASE RETURN A COPY OF THIS LETTER** with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

FORM PTO-1449 (modified)
To: U.S. Department of Commerce
(PW FORM PAT-1449)
Patent and Trademark Office



Atty.
Dkt. No.

M#

Client Ref.

306524

P-0381.020-US

Applicant: LOF et al.

Appln. No. 10/705,783

Filing Date: November 12, 2003

Examiner: Unknown

Group Art Unit: ~~1956~~ 2851

INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

Date: January 6, 2005

Page 1 of 1

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
D.R.	AR	4,390,273	06/1983	LOEBACH et al.	355	125	
	BR	6,236,634 B1	05/2001	LEE et al.	369	112	
	CR	2002/0020821 A1	02/2002	VAN SANTEN et al.	250	492	
	DR	2004/0119954 A1	06/2004	KAWASHIMA et al.	355	30	
D.R.	ER	2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
						Enclosed	No	Enclosed	No
D.R.	FR	WO 2004/053596 A2	06/2004	PCT	GRAUPNER	X			
	GR	WO 2004/053950 A1	06/2004	PCT	OWA	X			
	HR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.	X			
	IR	WO 2004/053952 A1	06/2004	PCT	MAGOME et al.	X			
	JR	WO 2004/053953 A1	06/2004	PCT	NEI et al.	X			
	KR	WO 2004/053954 A1	06/2004	PCT	NEI et al.	X			
	LR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.	X			
	MR	WO 2004/053956 A1	06/2004	PCT	NAGASAKA et al.	X			
	NR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.	X			
	OR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.	X			
	PR	WO 2004/053959 A1	06/2004	PCT	SHIRAI	X			
	QR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X			
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	SR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X			
	TR	JP 11-176727	07/1999	JAPAN	SHIRAISHI	X			
	UR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.	X			
D.R.	VR	JP 2004-193252	07/2004	JAPAN	Not Available	X			

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

WR

Examiner: *RND*

Date Considered: 5/6/2005

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.